

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Accompanying Divisional Application under 37 CFR 1.53:

Prior Application: M. ISHIBASHI et al
Serial No. 09/090,942
Filed: June 5, 1998

Group Art Unit: 2851
Examiner: P. Kim
For: ELECTRON EXPOSURE APPARATUS

2/A,
3/26/92
M. K. Redgen

PRELIMINARY AMENDMENT

Commissioner of Patents
Washington, D.C. 20231

January 18, 2002

Sir:

Prior to examination, please amend the above application
as follows.

IN THE SPECIFICATION

Page 1, before the first line, add the paragraph:

This is a continuation application of US Serial No.

09/090,942, filed on June 5, 1998.

IN THE CLAIMS

Cancel claims 1-23 without prejudice or disclaimer and
add new claims 24-28 as set forth below.

24. (New) A method of performing lithography on a
substrate using a resist film,

said method comprising the following steps:

exposing said resist film with electrons from a tip by
supplying a first bias voltage between said tip and said

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